

OUTLOOK FOR CMP CONSUMABLES

CMPUG April 12, 2018

Mike Corbett Linx Consulting Inc.

Outline



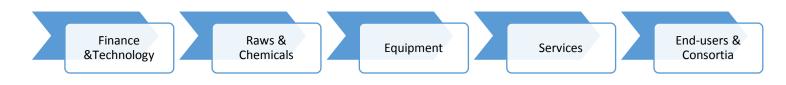
- Introduction to Linx Consulting
- Semi Industry Outlook
- Materials Challenges
- Impact on Suppliers
- Conclusions



Introduction to Linx Consulting

Linx Consulting





- 1. We help our clients to succeed by creating knowledge and developing unique insights at the intersection of electronic thin film processes and the chemicals industry on a global basis
- 2. The knowledge is based on a core understanding of the semiconductor device technology; manufacturing processes and roadmaps; and the global structural industry dynamics
- *3. This knowledge is leveraged to create advanced models, simulations and real-world forecasts*
- 4. Our perspectives are by direct research and leveraging our extensive experience throughout the global industry value chain



MSI Breakdown & Forecasts



and Understanding



Linx Consulting Service Portfolio



- Full Service
 - Forecast Service
 - Technology Trends
- Multi-Client Reports
 - IC Materials
 - CMP
 - Deposition
 - Patterning
 - Cleaning
 - Gases
 - Bulk Chemicals
 - Packaging
- Econometric Semiconductor Forecast
 - Financial planning
 - Sales and Operational planning
 - Forecasting

With Hilltop Economics LLC

- Conference Production
 - The Business of Cleans & SPCC

- Proprietary Projects
 - Market Planning
 - M & A
 - · Growth and Diversification
 - Supply Chain Optimization
 - Technology Commercialization
 - Strategic Planning
 - · Voice of the Customer
 - Market Diligence
- Cost Modeling
 - Client demand modeling
 - Product development
 - Bill of Materials quantification
 - With IC Knowledge, LLC
- Wafer Start Demand Forecasting
 - Device type and technology node



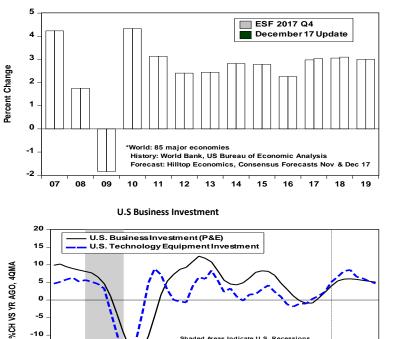
Semi Industry Outlook

Economic Drivers

18 19

6





Shaded Areas Indicate U.S. Recessions History: U.S. Bureau of Ecnomic Analysis, (\$)

Forecast: Hilltop Economics December 2017

11 12 13 14 15 16 17

-5

-10

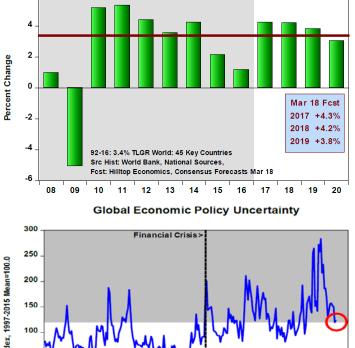
-15

-20

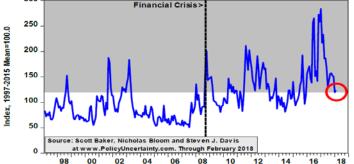
06 07

08 09 10

World* Real GDP Growth 2016: 2.3% 2017: 3.0% 2018: 3.1%



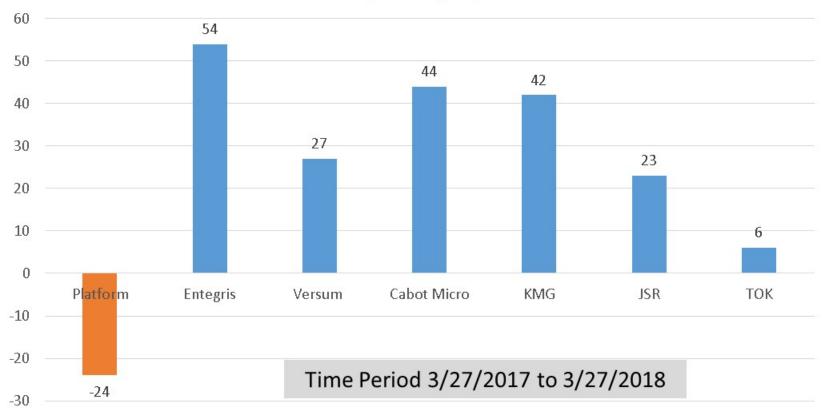
World* Real Investment



Linx WFM Equity Index



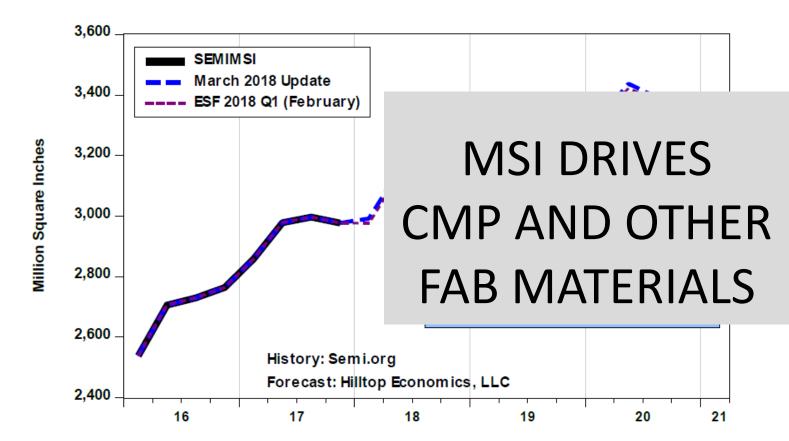
% Change in Equity Price





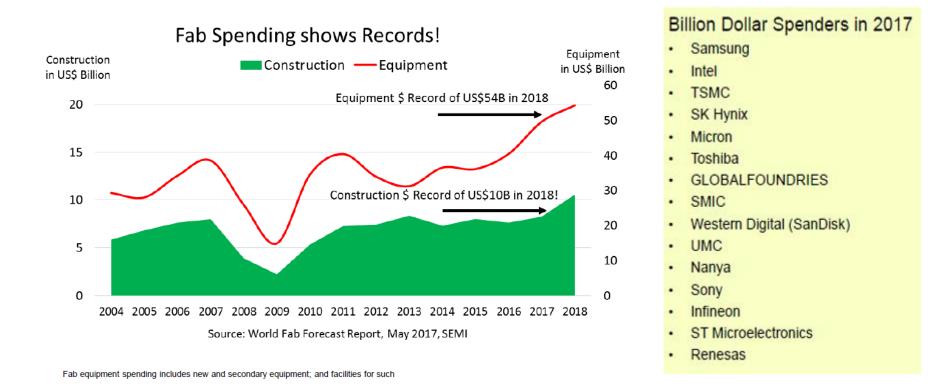


Semiconductor Forecast: ESF 2018 Q1



Record Levels of Capex





Capacity Utilization for 200mm and 300mm fabs > 95% in 2017

Key Growth Drivers: NAND, DRAM and Foundry



Driven by NAND, DRAM and Foundry

NAND

- Samsung Pyeongtaek P1
- SK Hynix M14 3D NAND line
- Micron Building 60 (Lehi) and Fab 10X in Singapore
- Toshiba/Flash Alliance Fab 2, Fab 6 and new R&D Center
- Intel Fab 68 in China

DRAM

- Samsung Pyeongtaek P1 and Line 15
- Micron Fab 15 (Hiroshima) and Fab 16
- SK Hynix M14

Foundry

- TSMC Fab 12, Fab 14 and Fab 15
- Samsung S2 and S3
- GLOBALFOUNDRIES Fab 1, Fab 8 and Fab 11
- SMIC Beijing B2 and B3, new Shanghai 300mm fab and Shenzhen 300mm fab
- UMC Fab 12A P5 and Xiamen fab



Fab Equipment Spending

Source: SEMI World Fab Forecast, December 2017

3DN and Logic driving growth. Vertical scaling helps drive Materials Growth



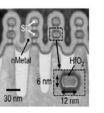
Materials Challenges

Materials Challenges

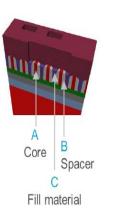


Demand Drivers

- CuBS demand increasing in Logic Interconnect
 - Limitations of current architectures
- FinFET gate deposition
 - GAA Nanowire develop
 - High mobility materials



- Memory technology extension
 - 3D-NAND growth
 - DRAM capacitor dielectric
 - Novel architectures
- Pitch doubling and quadrupling
 - Low temperature spacers
- Lithography aids



Opportunities

- Possible changes in conductor metal
 - Cu \Rightarrow Co Barrier \Rightarrow Co plating
- 3D-NAND aspect ratio
 - Hard mask technology
 - 2D stair-step
- Novel process development
 - Multi color, self aligning etch
 - CVD ⇔ Continuous etch
 - ALD ⇔ ALE
- Self Assembling Materials for selective processes
- Few new PVD applications
 - 3DXpoint / MRAM?
- Selective Deposition
 - Self Assembling Materials
 - Selective Deposition



Metal on metal

Dielectric on Dielectric



D : Dielectri M : Metal

Trends - WFM Spend at Advanced Nodes



Trends in Advanced Technology Wet Cleans

Wet chemical consumption per wafer is increasing

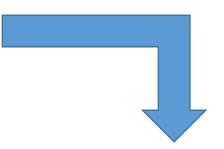
- · Proliferation of single-wafer processing, higher number of layers
- · Multi-step patterning, more complex process flows
- · Defect reduction, less recycle

Larger volumes increase scrutiny on chemical cost (\$)

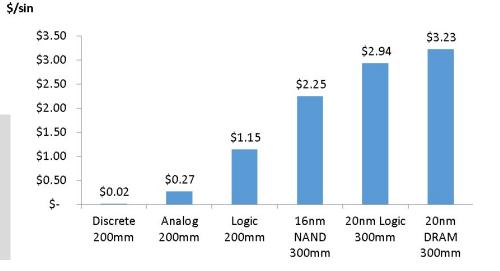


Trend driven by:

- Increased # of interconnect and FEOL layers
- RMG process
- Multi-Patterning
- New materials integration



Bill of Materials – Si not Included



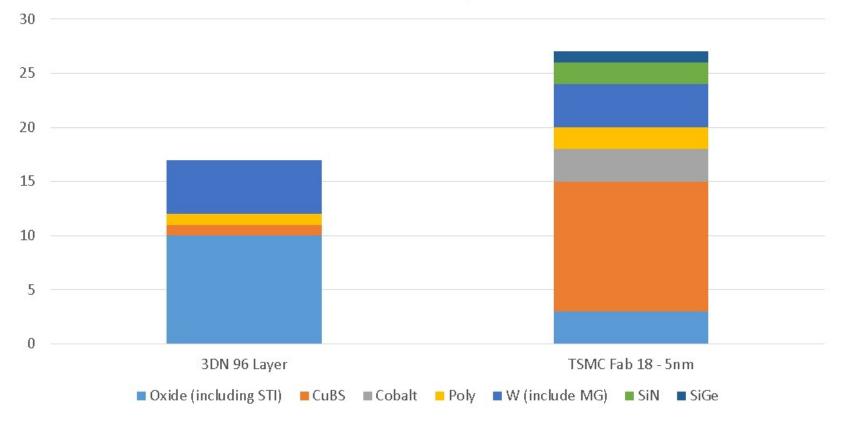
Source: Linx, IC Knowledge, Intel



CMP Benefits from New Devices

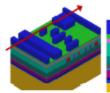


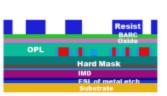
CMP Steps



Planarity Considerations in SADP for Advanced BEOL Patterning







1.1(a) A fully planarized lithography stack

1.1(b) Non-mandrel pattern transferred into the hard mask



1.1(c) Mandrel pattern transferred into the hard mask





1.2(a) A lithography stack with a smooth

. .

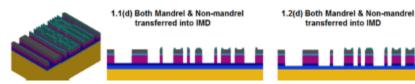
1.2(b) Non-mandrel pattern transferred

1.2(c) Mandrel pattern transferred into

the hard mask

into the hard mask

coating OPL



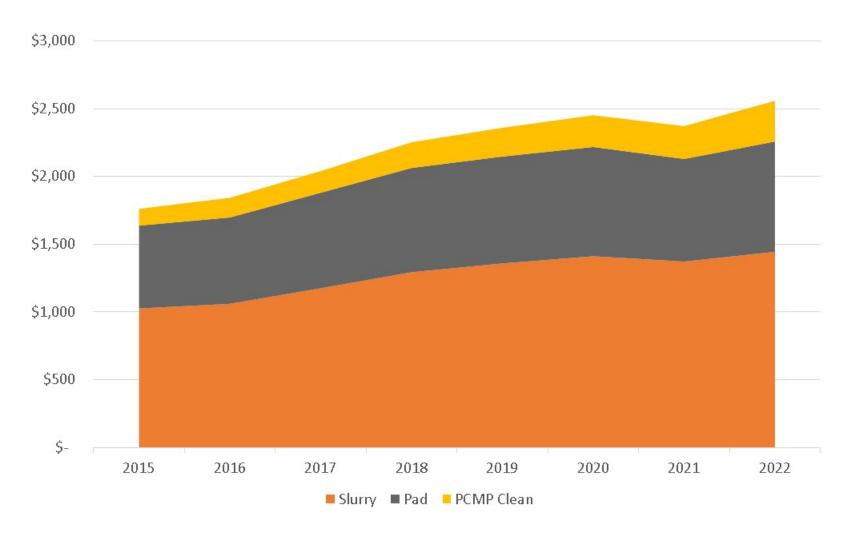
- CNSE have shown the impact of gap-fill planarity on SADP process for advanced 7nm/5 nm technology
- Multiple patterning has been the main stream integration scheme in the sub 14 nm before the maturity of EUV lithography
- Among all the practical schemes, SADP not only simplified the overlay control, but also provides a better RC performance over the LELE scheme
- Therefore, minimizing the number of cuts in the SADP integration became important to HVM
- CNSE demonstrated that a robust SADP process through insertion of etch stop layer (ESL) between two coatings of organic polymer layers

Source: Albany Nanotech/IBM





Slurry, Pad & PCMPC Forecast (\$M)





Impact on Suppliers

Regional & Structural Trends



- Cabot Microelectronics NexPlanar
 - Fujimi Collaboration
- FujiFilm EM Ultra Pure + Wako
- Wonik Nova-Kem
- NATA Kempur
- Air Liquide AirGas + Voltaix
- Air Products Versum Materials spinout
- SK OCIM + Tri-Chem

- Dow Chemical DuPont + Dow Corning
- Global Wafer -SunEdison
- Yoke UPChem
- Versum Dynaloy
- SK Holding LG Siltron + OCIM
- Linde + Praxair
- Avantor Gelest

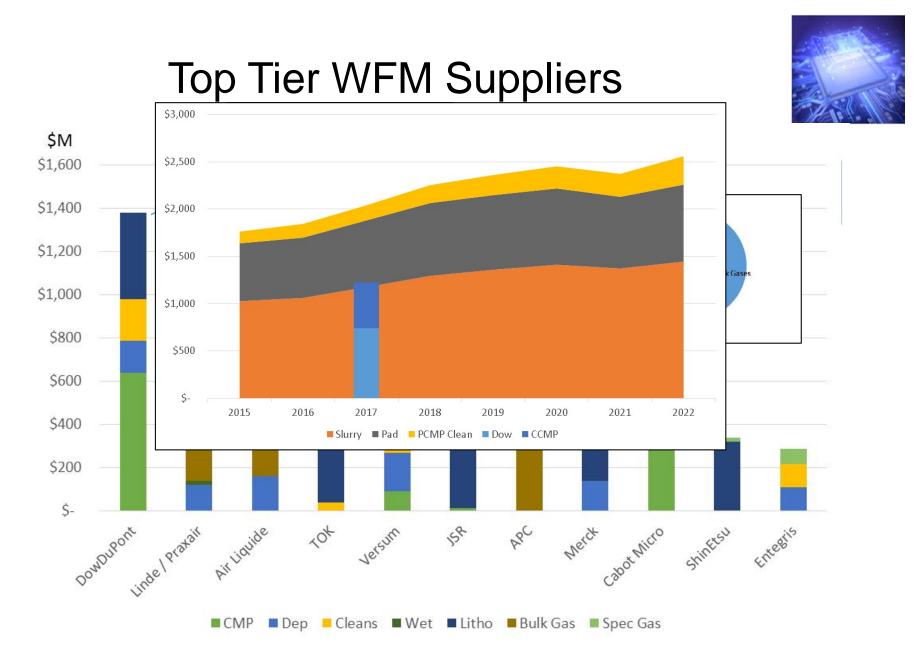
China

- Leveraged government equity positions to enable significant sized acquisitions
- Continued acquisition activity from multiple companies.
- Acquisitions along the line of key product areas:
 - Silicon
 - Gases
 - Lithography materials
 - Advanced deposition materials

Korea

- Korean companies also looking to change business model
- Gain international market
 access







Conclusions

Conclusions



- Sustainable strong growth outlook anticipated for several years
- 3D structures and new materials will continue to drive semiconductor technology advancement at 1Xnm and beyond.
- 200mm and older wafer fab is expected to remain at high levels of capacity utilization over the next several years. Productivity will be a major driver
- Concentrated customer base and tool supplier base, along with increasing barriers to serve end-users will drive WFM consolidation
- New capacity in China will enable new suppliers who will initially compete with special commodities
- Expect Korea to focus more effort on specialty chemicals